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zinc, nickel, iron, niobium, molybdenum, titanium, nickel/chromium alloy, iron/nickel/chromium alloy and aluminum, a dielectric material deposited on the first metal layer and having a thickness of from about 0.03 to about 2 microns and wherein the dielectric material contains a cation other than that of the metal from which the metal foil is formed, and a second metal layer, said first and second metal layers each having an exposed surface.

Add Claims 36-46 which reads as follows:

- --36. The layered structure according to Claim 35 wherein said second metal layer is patterned.
- 37.. A layered structure for forming a thin layer capacitor comprising:
  - a flexible polymer support sheet.
- an un-patterned first metal layer formed on said flexible polymer support sheet, said first metal layer being release-able from said support sheet, the metal being selected from the group consisting of copper, zinc, nickel, iron, niobium, molybdenum, titanium, nickel/chromium alloy, iron/nickel/chromium alloy and aluminum.
- a dielectric layer formed on said un-patterned first metal layer between about 0.03 and about 2 microns thick, and
- a second metal—layer formed on said flexible polymer support sheet, the metal being selected from the group consisting of copper, zinc, nickel, iron, niobium, molybdenum, titanium, nickel/chromium alloy, iron/nickel/chromium alloy and aluminum, said second metal layer having an exposed surface.
- 38. The layered structure according to Claim 37 wherein said support sheet is polymeric material.
- 39. The layered structure according to Claim 37 wherein said second metal layer is patterned..
- 40. A layered structure for acting as or forming at least one thin layer capacitor comprising in sequence a first metal layer selected from the group consisting of copper, zinc, nickel, iron, niobium, molybdenum, titanium, nickel/chromium alloy, iron/nickel/chromium alloy and aluminum, a dielectric material deposited on the first metal layer and having a thickness of from about 0.03 to about 2, a second metal layer, and a barrier lalyer between about 0.01 and about 0.08 microns thick between said first metal layer and said dielectric material layer.

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- 41. The layered structure according to Claim 40 wherein said barrier layer is formed of material selected from the group consisting of tungsten oxide, strontium oxide, and mixed tungsten/strontium oxides.
- 42. The layered structure according to Claim 40 wherein said barrier layer is formed of material selected from the group consisting of BAWO<sub>4</sub>, silica, alumina, nickel and platinum.
- 43. The layered structure according to Claim 40 wherein said barrier layer is formed of material selected from the group consisting of ceria and  $Sr_{1-x}Ba_xWO_4$ .
- 44. A layered structure for acting as or forming at least one thin layer capacitor comprising in sequence a first metal layer selected from the group consisting of copper, zinc, nickel, iron, niobium, molybdenum, titanium, nickel/chromium alloy, iron/nickel/chromium alloy and aluminum, a dielectric material deposited on the first metal layer and having a thickness of from about 0.03 to about 2 microns, a second metal layer, and an adhesion layer between abnout 0.0001 and about 0.05 microns thick between said dielectric material layer and said second metal layer.
- 45. The layered structure according to Claim 44 wherein said adhesion layer is a functionally gradient material..
- 46. A layered structure for acting as or forming at least one thin layer capacitor comprising in sequence a first metal layer selected from the group consisting of copper, zinc, nickel, iron, niobium, molybdenum, titamum, nickel/chromium alloy, iron/nickel/chromium alloy and aluminum, a dielectric material deposited on the first metal layer and having a thickness of from about 0.03 to about 2 microns, and a second metal layer, said dielectric material layer being chemically doped to be lossy having an electrical conductivity value of from about 10<sup>-1</sup> to about 10<sup>-5</sup> amperes per cm<sup>2</sup>.

## <u>REMARKS</u>

Claims 2-3. 5-35 are pending in the present application. Claims 8, 9, and 24-28 are deleted with this amendment; Claims 36-46 are added with entry of this Amendment.

Claims 40, 44, and 46 correspo